

WEST Search History

DATE: Friday, July 26, 2002

Set Name Query

side by side

Hit Count Set Name

result set

DB=USPT,PGPB; PLUR=YES; OP=ADJ

L18	((SiON or (silicon near2 oxynitride)) same (anneal\$3 or consolidat\$3 or firing of fire or fired or bake or baked or baking or (heat\$3 near2 treat\$4)) same (consolidat\$6 or condens\$7 or densify\$4 or compact\$4) same (T or temperature) same (O2 or "O.sub.2" or oxygen))	7	L18
L17	((liquid crystal) with (alignment)) and (polyimide with align\$5 with (rub\$4 and light and (UV or ultraviolet)))	21	L17
L16	L13 and (semiconductor or SiN or SiNx or (silicon nitride) or polysilicon)	87	L16
L15	L12 and (semiconductor or SiN or SiNx or (silicon nitride) or polysilicon)	225	L15
L14	L13 and L3	17	L14
L13	L12 same (alter\$5 or adjust\$5 or modify\$3 or chang\$3 or increas\$3 or decreas\$3 or modification)	178	L13
L12	((ARC or ((AR or antireflect\$4) near3 (coat\$3 or film or layer)) or SiO2 or "SiO.sub.2" or (silicon \$2oxide) or SiON or SiONH or SiOHN or (silicon near2 oxynitride)) same (anneal\$3 or consolidat\$3 or firing of fire or fired or bake or baked or baking or (heat\$3 near2 treat\$4)) same (((optical near2 (quality or propert\$4)) or (refract\$4 near3 index) or (extinct\$4 near3 coefficient))))	444	L12

DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

L11	L10 and semiconductor	28	L11
L10	L7 and ((optical near2 (quality or propert\$4)) or (refract\$4 near3 index) or (extinct\$4 near3 coefficient))	206	L10
L9	L8 and ((optical near2 (quality or propert\$4)) or (refract\$4 near3 index) or (extinct\$4 near3 coefficient))	6	L9
L8	L7 and semiconductor and (SiN or SiNx or (silicon nitride) or polysilicon)	1024	L8
L7	((ARC or ((AR or antireflect\$4) near3 (coat\$3 or film or layer)) or SiO2 or "SiO.sub.2" or (silicon \$2oxide) or SiON or SiONH or SiOHN or (silicon near2 oxynitride)) same (anneal\$3 or consolidat\$3 or firing of fire or fired or bake or baked or baking or (heat\$3 near2 treat\$4)))	12037	L7

DB=USPT,PGPB; PLUR=YES; OP=ADJ

L6	L5 and ((optical near2 (quality or propert\$4)) or (refract\$4 near3 index) or (extinct\$4 near3 coefficient))	37	L6
L5	L4 and semiconductor and (SiN or SiNx or (silicon nitride) or polysilicon)	172	L5

L4	L3 and ((ARC or ((AR or antireflect\$4) near3 (coat\$3 or film or layer)) or SiO2 or "SiO.sub.2" or (silicon \$2oxide) or SiON or SiONH or SiOHN or (silicon near2 oxynitride)) same (anneal\$3 or consolidat\$3 or firing of fire or fired or bake or baked or baking or (heat\$3 near2 treat\$4)))	360	L4
L3	((427/569).icls. or (427/579).icls. or (427/162).icls. or (427/255.29).icls. or (427/255.37).icls. or (427/372.2).icls. or (427/397.7).icls. or (438/786).icls. or (438/787).icls. or (438/788).icls. or (438/791).icls. or ((438/792)!.ICLS.))	3411	L3
<i>DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
L2	(Chiou or Jang) and ((ARC or ((AR or antireflect\$4) near3 (coat\$3 or film or layer))) same (anneal\$3 or consolidat\$3 or firing of fire or fired or bake or baked or baking or (heat\$3 near2 treat\$4)))	1	L2
<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>			
L1	(Chiou.in. or Jang.in.) and ((ARC or ((AR or antireflect\$4) near3 (coat\$3 or film or layer))) same (anneal\$3 or consolidat\$3 or firing of fire or fired or bake or baked or baking or (heat\$3 near2 treat\$4)))	2	L1

END OF SEARCH HISTORY